EE 330 Lecture 36

Cascaded Amplifiers

Amplifier Biasing

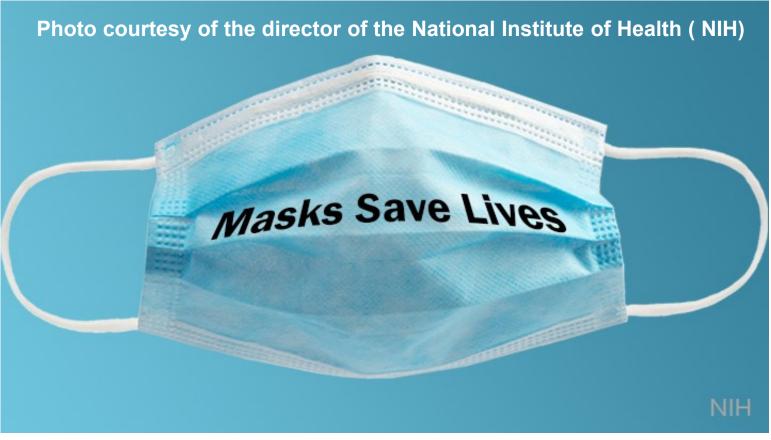
Other Amplifer Structures

Frequency-Dependent Performance of Amplifiers

Parasitic Capacitances in MOS Devices

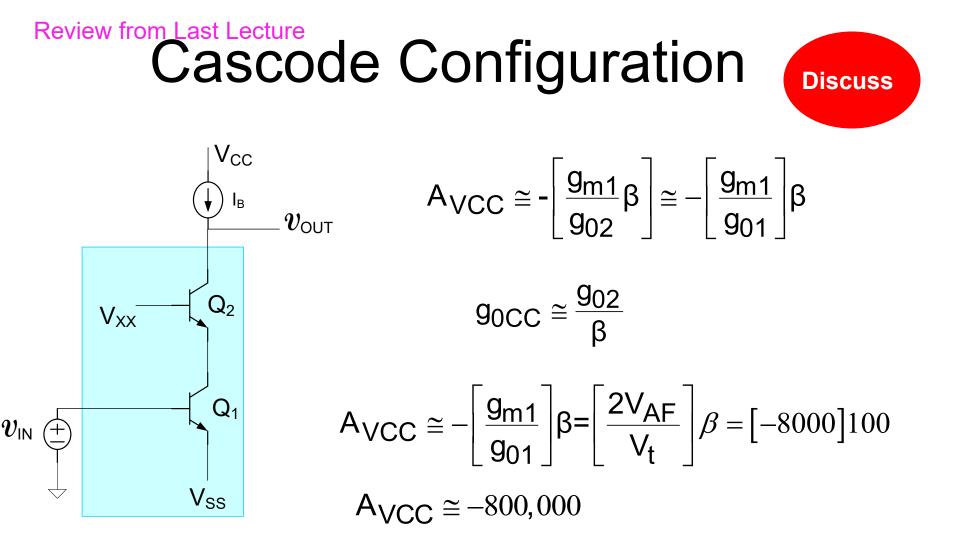
Exam Schedule

Exam 1 Exam 2 Exam 3 Final Friday Sept 24 Friday Oct 22 Friday Nov 19 Tues Dec 14 12:00 p.m.



As a courtesy to fellow classmates, TAs, and the instructor

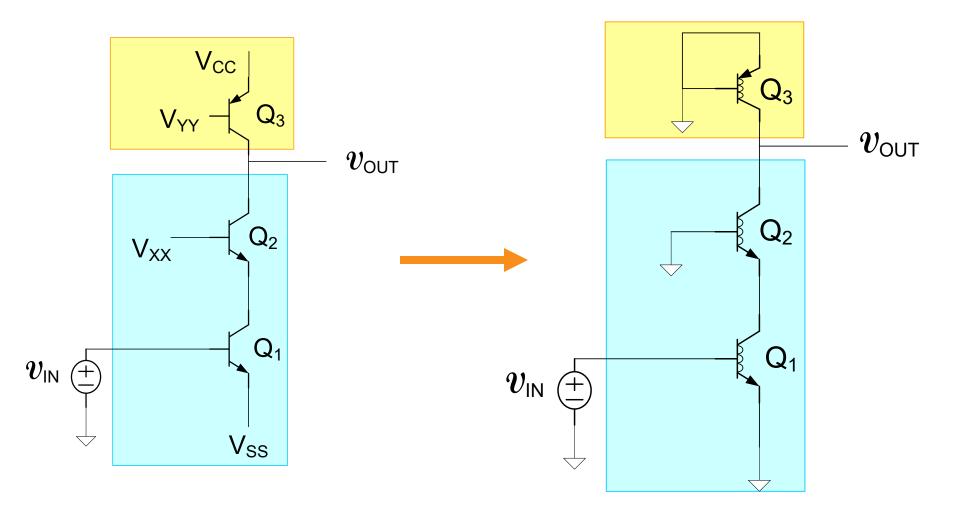
Wearing of masks during lectures and in the laboratories for this course would be appreciated irrespective of vaccination status



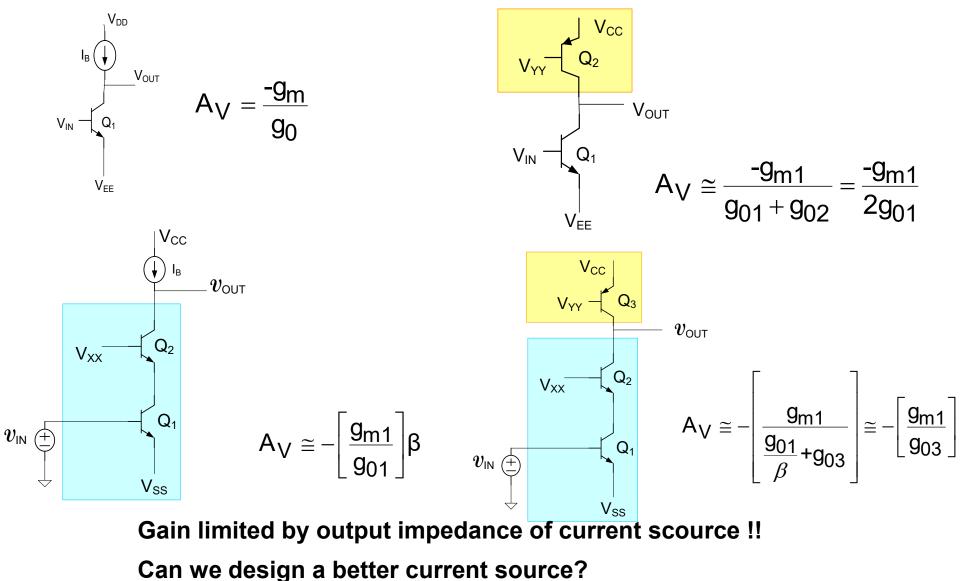
This gain is very large and only requires two transistors!

What happens to the gain if a transistor-level current source is used for I_B ?

Review from Last Lecture Cascode Configuration

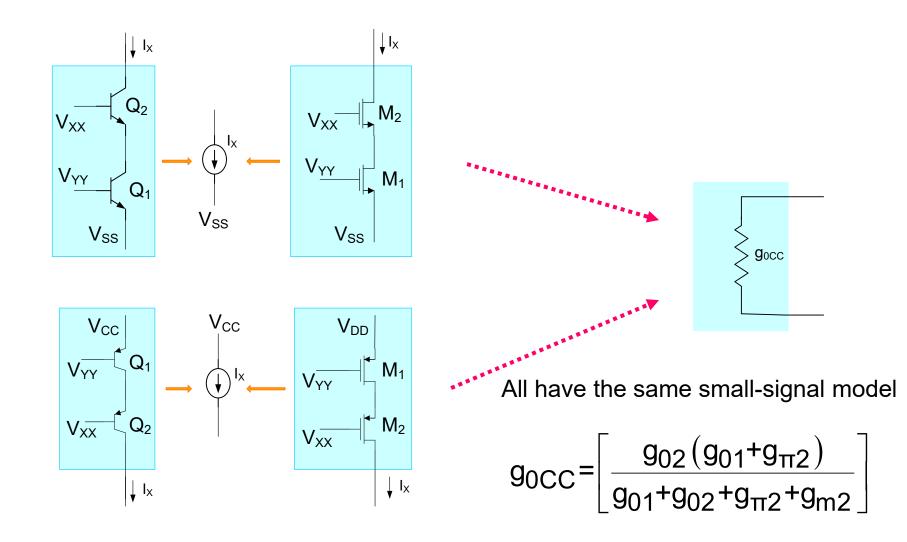


Review from Last Lecture Cascode Configuration Comparisons



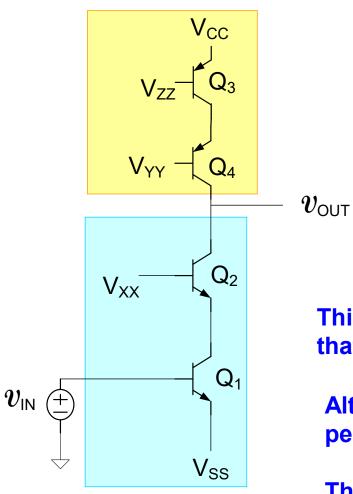
In particular, one with a higher output impedance?

Cascode current sources



Review from Last Lecture Cascode Configuration





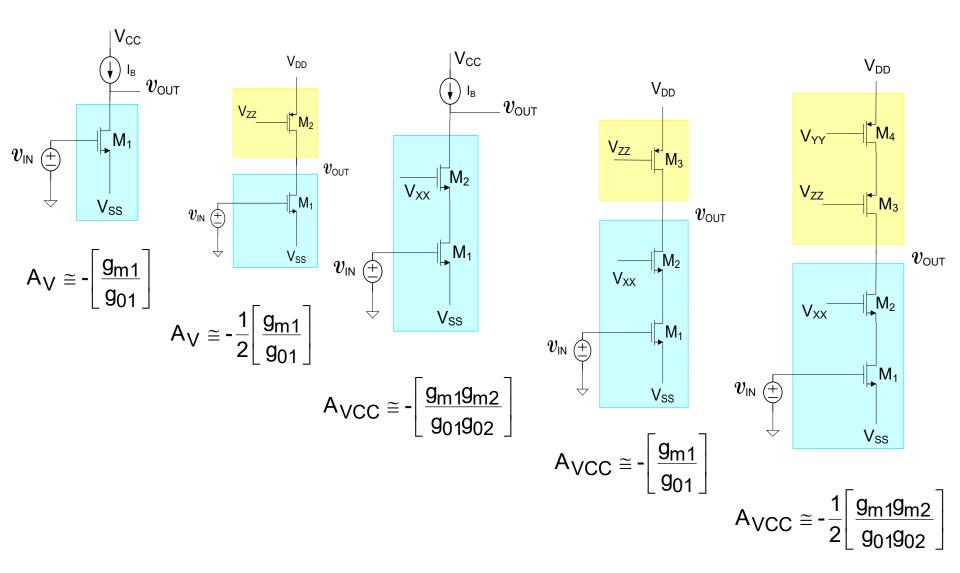
$$A_{V} = -\left[\frac{g_{m1}}{g_{01}}\right]\frac{\beta}{2}$$
$$A_{V} = -[8000]\frac{100}{2} \approx -400,000$$

This gain is very large and is a factor of 2 below that obtained with an ideal current source biasing

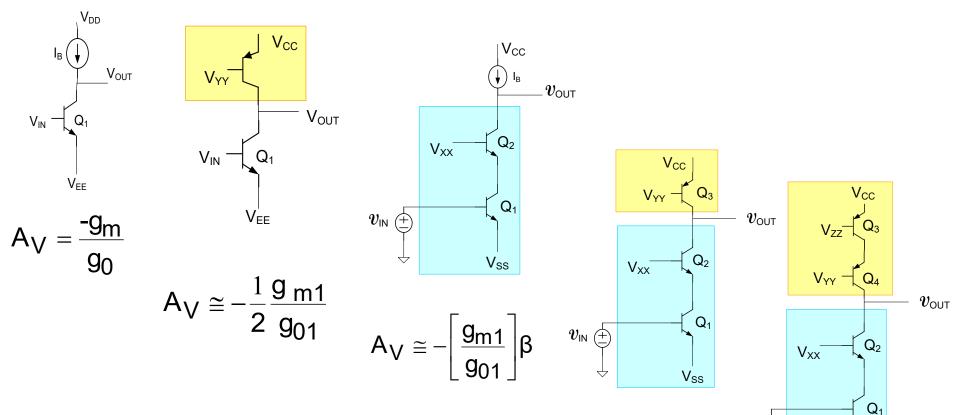
Although the factor of 2 is not desired, the performance of this circuit is still very good

This factor of 2 gain reduction is that same as was observed for the CE amplifier when a transistorlevel current source was used

Review from Last Lecture High Gain Amplifier Comparisons (n-ch MOS)



Review from Last Lecture High Gain Amplifier Comparisons (BJT)



 $A_V \cong - \left| \frac{g_{m1}}{g_{01}} \right|$

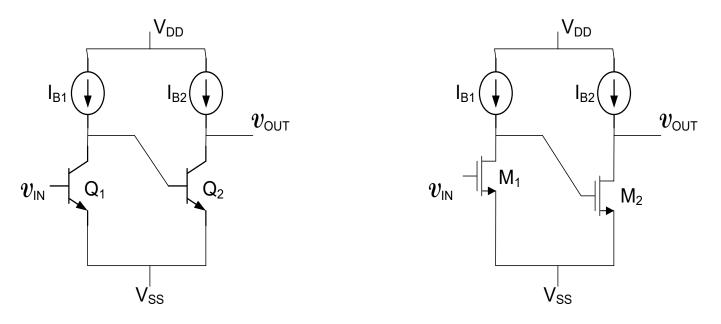
 $v_{ ext{in}} \oplus$

 $A_V = -$

 V_{SS}

 $\left| \frac{g_{m1}}{g_{m1}} \right| \frac{\beta}{2}$

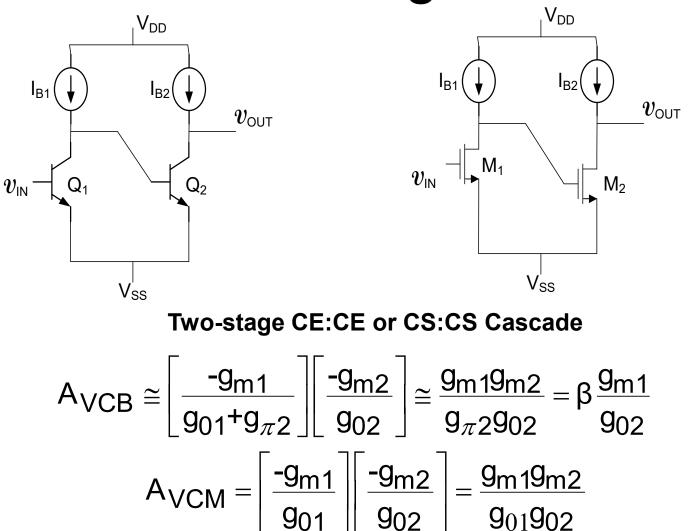
- Single-ended high-gain amplifiers inherently difficult to bias (because of the high gain)
- Biasing becomes practical when used in differential applications
- These structures are widely used but usually with differential inputs



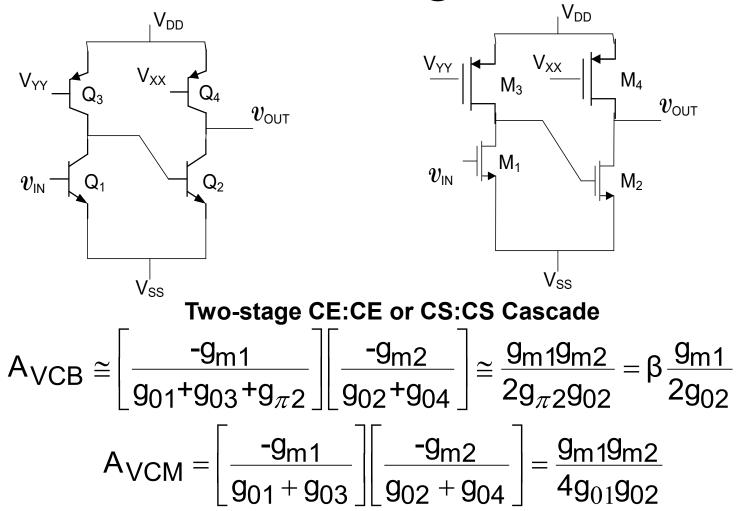
Two-stage CE:CE or CS:CS Cascade

 $A_{VCB} = ?$

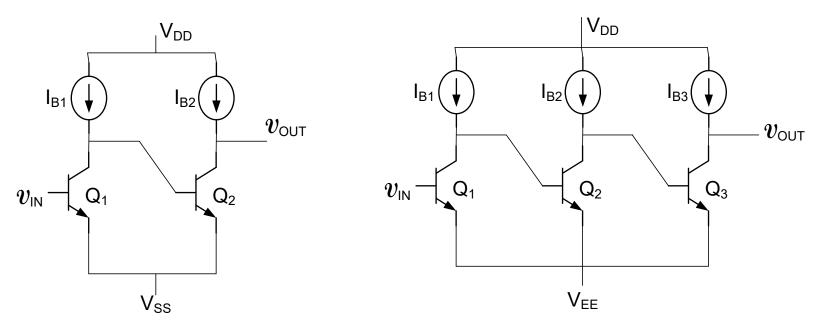
 $A_{VCM} = ?$



- Significant increase in gain
- Gain is noninverting
- Comparable to that obtained with the cascode but noninverting



Note factor or 2 and 4 reduction in gain due to actual current source bias

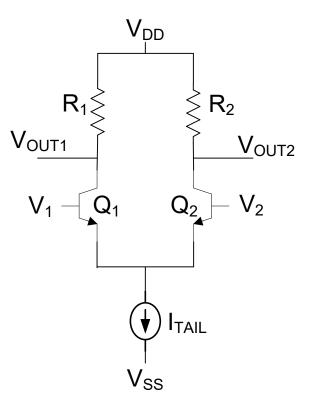


Two-stage CE Cascade

Three-stage CE Cascade

- Large gains can be obtained by cascading
- Gains are multiplicative (when loading is included)
- Large gains used to build "Op Amps" and feedback used to control gain value
- Some attention is needed for biasing but it is manageable
- Minor variant of the two-stage cascade often used to build Op Amps
- Compensation of two-stage cascade needed if feedback is applied to maintain stability
- For many years three or more stages were seldom cascaded because of challenges in compensation to maintain stability though recently some industrial adoptions

Differential Amplifiers



Basic operational amplifier circuit

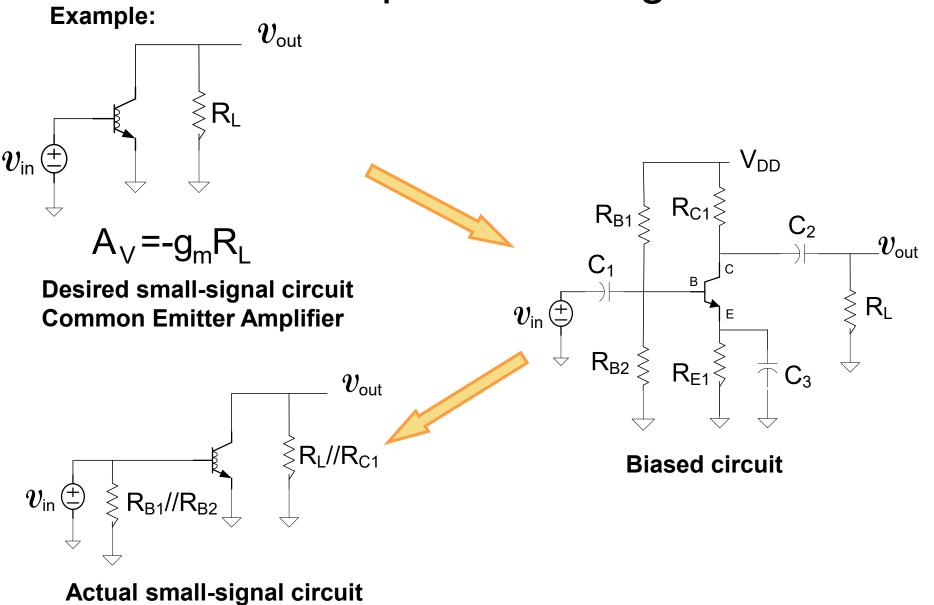
Amplifier biasing is that part of the design of a circuit that establishes the desired operating point (or Q-point)

Goal is to invariably minimize the impact the biasing circuit has on the small-signal performance of a circuit

Usually at most 2 dc power supplies are available and these are often fixed in value by system requirements – this restriction is cost driven

Discrete amplifiers invariable involve adding biasing resistors and use capacitor coupling and bypassing

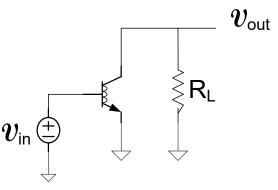
Integrated amplifiers often use current sources which can be used in very large numbers and are very inexpensive



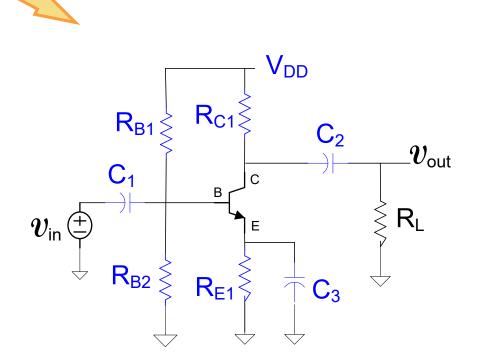
$$A_{V} = -g_{m} (R_{L} //R_{C1})$$

Biasing components shown in blue

Example:

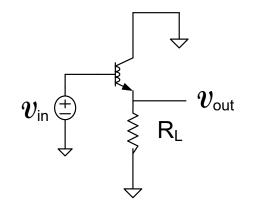


Desired small-signal circuit Common Emitter Amplifier

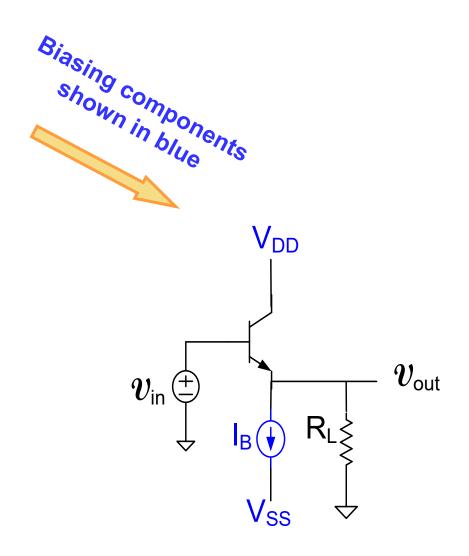


Biased small-signal circuit

Example:

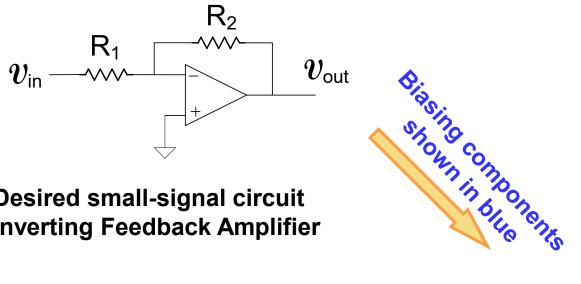


Desired small-signal circuit Common Collector Amplifier

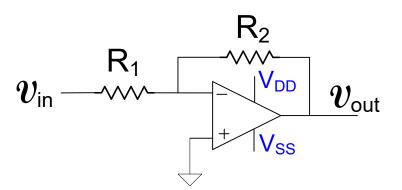


Biased circuit

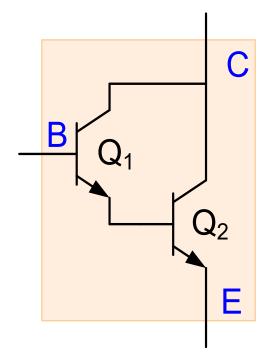
Example:

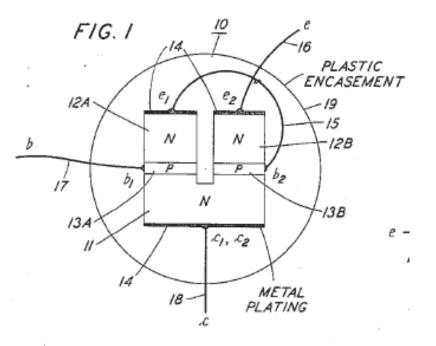


Desired small-signal circuit Inverting Feedback Amplifier



Biased circuit





Darlington Configuration

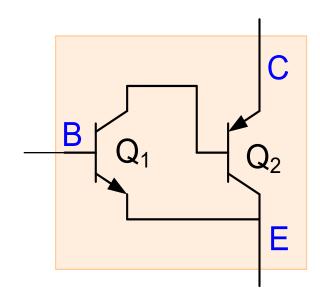


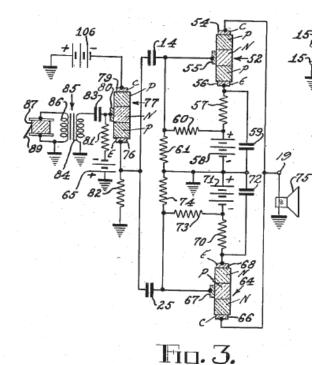
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SEMICONDUCTOR SIGNAL TRANSLATING DEVICE

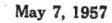
Filed May 9, 1952

- Current gain is approximately β²
- Two diode drop between B_{eff} and E_{eff}





Sziklai Pair



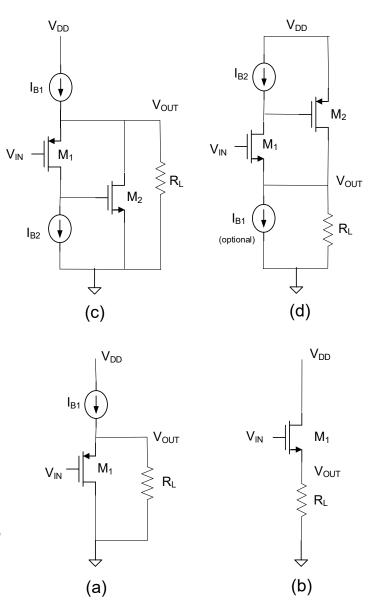
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PUSH-PULL AMPLIFIER WITH COMPLEMENTARY TYPE TRANSISTORS

Filed Nov. 7, 1952

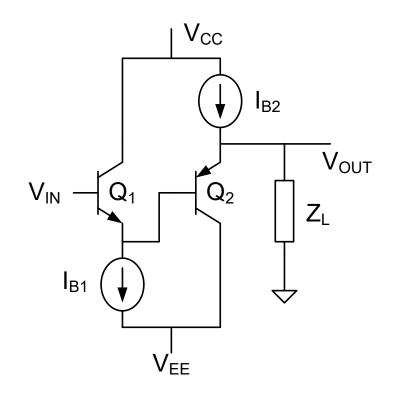
- Gain similar to that of Darlington Pair
- Current gain is approximately $\beta_n \beta_p$
- Current gain will not be as large when $\beta_p < \beta_n$
- Only one diode drop between B_{eff} and E_{eff}

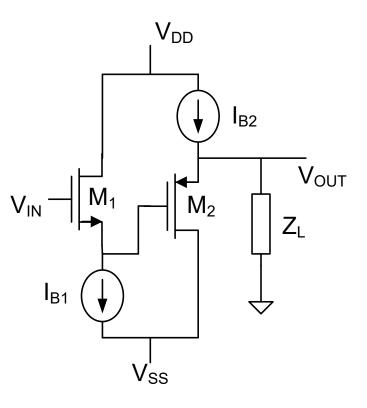


Buffer and Super Buffer

- Voltage shift varies with V_{IN} in buffer
- Current through shift transistor is constant for Super Buffer as V_{IN} changes so voltage shift does not change with V_{IN}
- Same nominal voltage shift

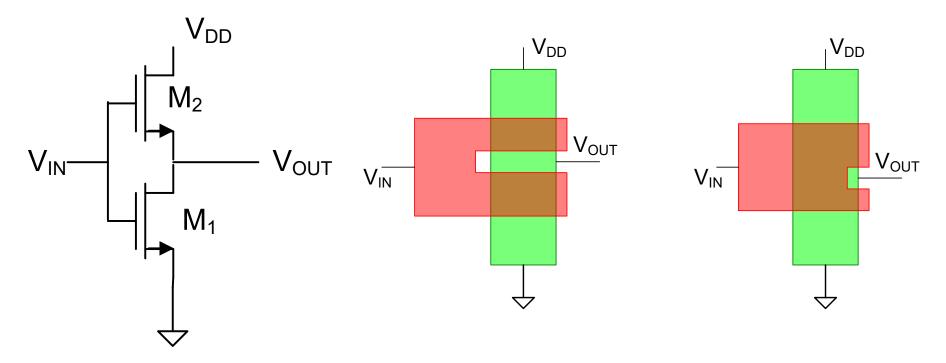
Low offset buffers





- Actually a CC-CC or a CD-CD cascade
- Significant drop in offset between input and output
- Biasing with DC current sources
- Can Add Super Buffer to Output

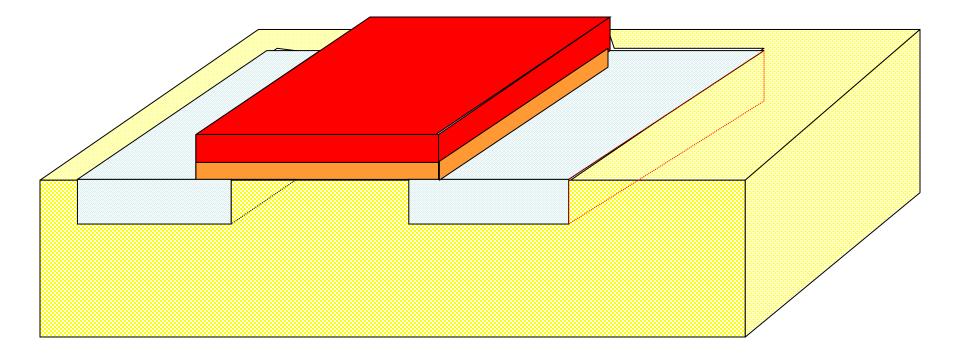
Voltage Attenuator



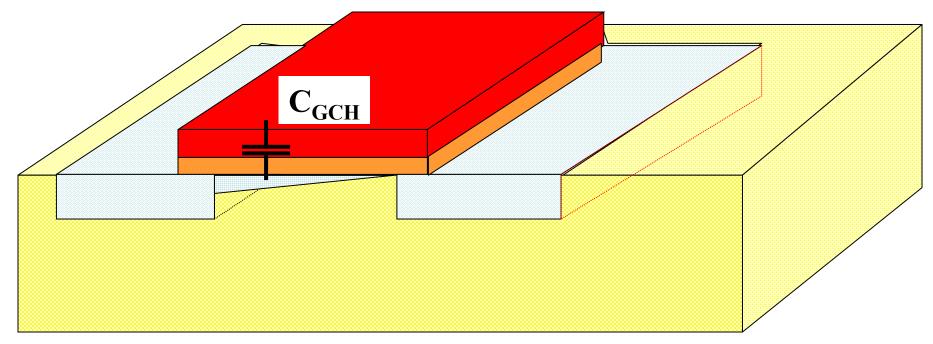
- Attenuation factor is quite accurate (Determined by geometry)
- Infinite input impedance
- M₁ in triode, M₂ in saturation
- Actually can be a channel-tapped structure

Frequency-Dependent Performance of Amplifiers

Parasitic Capacitors in MOSFET

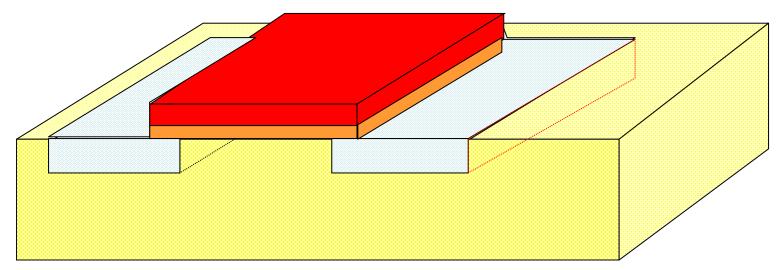


Parasitic Capacitors in MOSFET

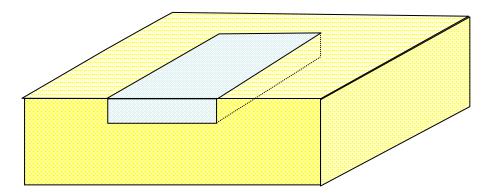


- This capacitance was modeled previously and exists when the transistor is operating in triode or saturation
- But there are others that also affect high-frequency or high-speed operation

Parasitic Capacitors in MOSFET

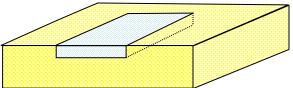


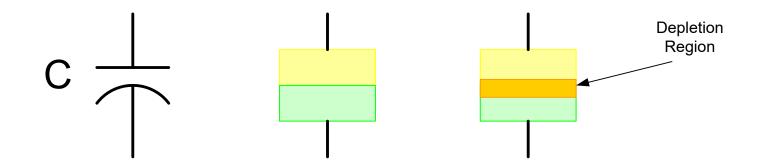
Recall that pn junctions have a depletion region!

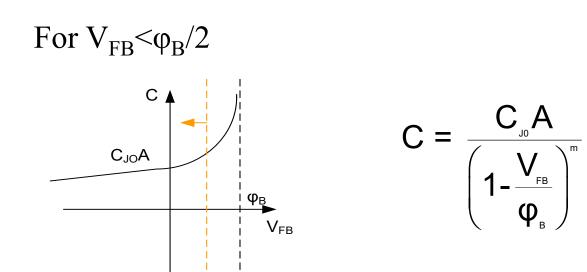


Parasitic Capacitors in MOSFET

pn junction capacitance

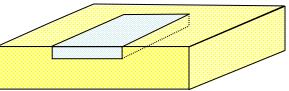




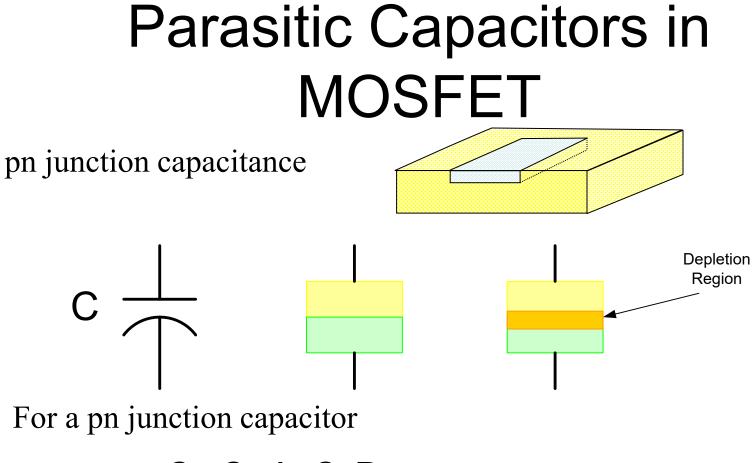


Parasitic Capacitors in MOSFET

pn junction capacitance



The bottom and the sidewall:



 $C_{J} = C_{BOT} A + C_{SW} P$ $C_{BOT} = \frac{C_{BOT0}}{\left(1 - \frac{V_{FB}}{\phi_{B}}\right)^{m}} \qquad C_{SW} = \frac{C_{SW0}}{\left(1 - \frac{V_{FB}}{\phi_{B}}\right)^{m}}$

 C_{BOT} and C_{SW} are capacitance densities

A : Junction Area P: Junction Perimeter V_{FB}: forward bias on junction

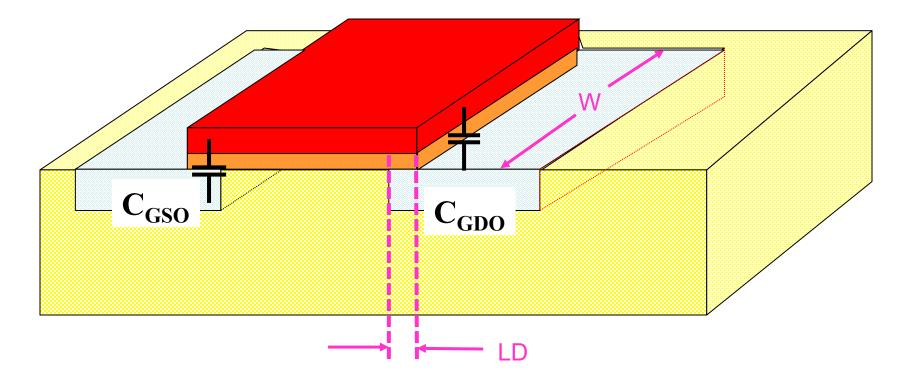
Model Parameters:

 $\{C_{BOT0},C_{SW0},\phi_B,m\}$

Types of Capacitors in MOSFETs

- 1. Fixed Capacitors
- a. Fixed Geometry
 - b. Junction
 - 2. Operating Region Dependent

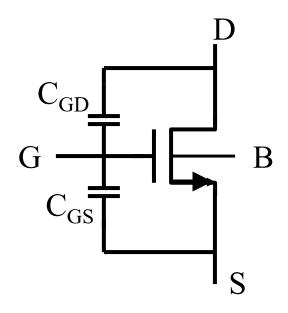
Parasitic Capacitors in MOSFET Fixed Capacitors – Fixed Geometry



Overlap Capacitors: C_{GDO} , C_{GSO} L_D: lateral diffusion

Cap Density: C_{OX}

Parasitic Capacitance Summary (partial)



	Cutoff	Ohmic	Saturation
C _{GS}	CoxWL _D	CoxWL _D	CoxWL _D
	CoxWL _D	CoxWL _D	CoxWL _D

 L_{D} is a model parameter

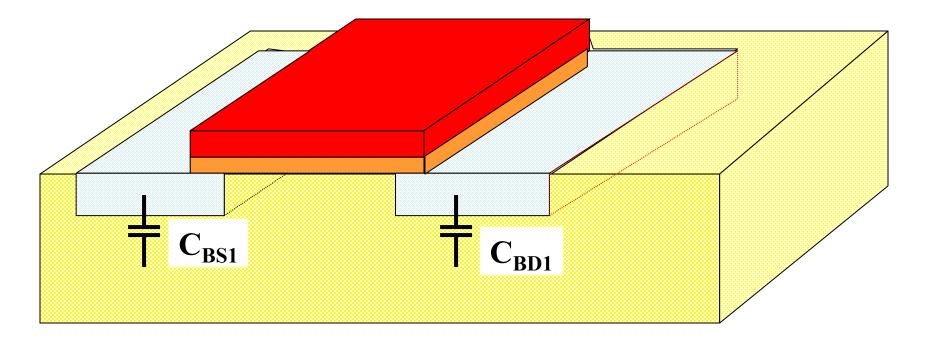
Overlap Capacitance Model Parameters

CAPACITANCE PARAMETE	RS N+ I	P+ POLY	M1	M2	MЗ	М4	М5	М6	RW	D N W M5P	ΝW	UNITS
Area (substrate)	942 1	L163 106	34	14	9	6	5	3	_	123	125	aF/um^2
Area (N+active)		8484		20	13	11	9	8				aF/um^2
Area (P+active)		8232										aF/um^2
Area (poly)			66	17	10	7	5	4				aF/um^2
Area (metal1)				37	14	9	6	5				aF/um^2
Area (metal2)					35	14	9	6				aF/um^2
Area (metal3)						37	14	9				aF/um^2
Area (metal4)							36	14				aF/um^2
Area (metal5)								34		9	84	aF/um^2
Area (r well)	920											aF/um^2
Area (d well)									582			aF/um^2
Area (no well)	137											aF/um^2
Fringe (substrate)	212	235	41	35	29	21	14					aF/um
Fringe (poly)			70	39	29	23	20	17				aF/um
Fringe (metal1)				52	34		22	19				aF/um
Fringe (metal2)					48	35	27	22				aF/um
Fringe (metal3)						53	34	27				aF/um
Fringe (metal4)							58	35				aF/um
Fringe (metal5)								55				aF/um
Overlap (N+active)		89.	5									aF/um
Overlap (P+active)		73	7)									aF/um

Types of Capacitors in MOSFETs

- 1. Fixed Capacitors
 - a. Fixed Geometry
- b. Junction
 - 2. Operating Region Dependent

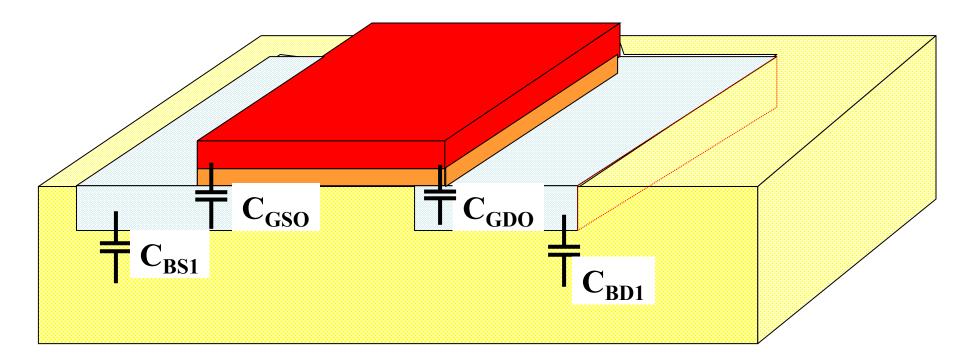
Parasitic Capacitors in MOSFET Fixed Capacitors-Junction



Junction Capacitors: C_{BS1}, C_{BD1}

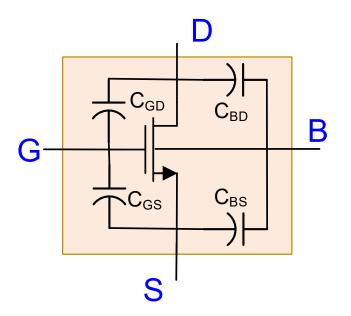
Parasitic Capacitors in MOSFET

- Fixed Capacitors



Overlap Capacitors: C_{GDO} , C_{GSO} Junction Capacitors: C_{BS1} , C_{BD1}

Fixed Parasitic Capacitance Summary



 C_{BOT} and C_{SW} are model parameters

	Cutoff	Ohmic	Saturation		
C _{GS}	CoxWL _D	CoxWL _D	CoxWL _D		
C _{GD}	CoxWL _D	CoxWL _D	CoxWL _D		
C _{BG}					
C _{BS}	$C_{BS1} = C_{BOT}A_S + C_{SW}P_S$	$C_{BS1} = C_{BOT}A_S + C_{SW}P_S$	$C_{BS1} = C_{BOT}A_S + C_{SW}P_S$		
C _{BD}	$C_{BD1} = C_{BOT}A_D + C_{SW}P_D$	$C_{BD1} = C_{BOT}A_D + C_{SW}P_D$	$C_{BD1} = C_{BOT}A_D + C_{SW}P_D$		

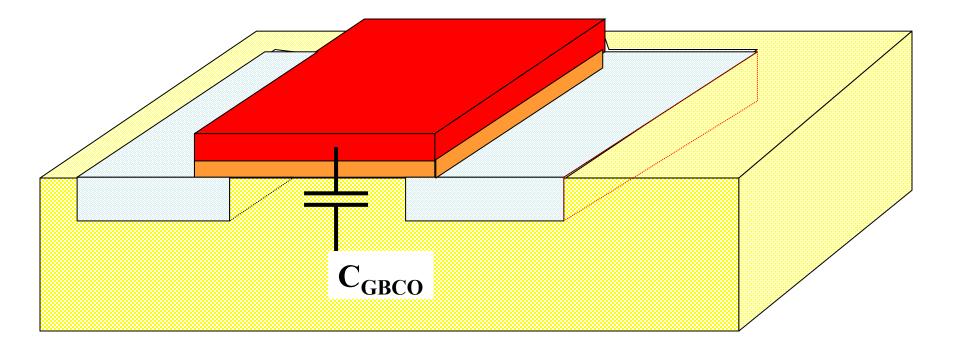
C_{BOT} and C_{SW} model parameters

CAPACITANCE PARAMETERS N+ P+ POLY	M1	М2	МЗ	M4	М5	Μ6	R_W	D_N_W M5F	N_W	UNITS
Area (substrate) 942(1163)106	34	14	9	6	5	3		123	125	aF/um^2
Area (N+active) 8484	55	20	13	11	9	8				aF/um^2
Area (P+active) 8232										aF/um^2
Area (poly)	66	17	10	7	5	4				aF/um^2
Area (metal1)		37	14	9	6	5				aF/um^2
Area (metal2)			35	14	9	6				aF/um^2
Area (metal3)				37	14	9				aF/um^2
Area (metal4)					36	14				aF/um^2
Area (metal5)						34		9	84	aF/um^2
Area (r well) 920										aF/um^2
Area (d well)							582			aF/um^2
Area (no well) 137										aF/um^2
Fringe (substrate) (212)(235)	41	35	29	21	14					aF/um
Fringe (poly)	70	39	29	23	20	17				aF/um
Fringe (metal1)		52	34		22	19				aF/um
Fringe (metal2)			48	35	27	22				aF/um
Fringe (metal3)				53	34	27				aF/um
Fringe (metal4)					58	35				aF/um
Fringe (metal5)						55				aF/um
Overlap (N+active) 89	5									aF/um
Overlap (P+active) 73	7									aF/um

Types of Capacitors in MOSFETs

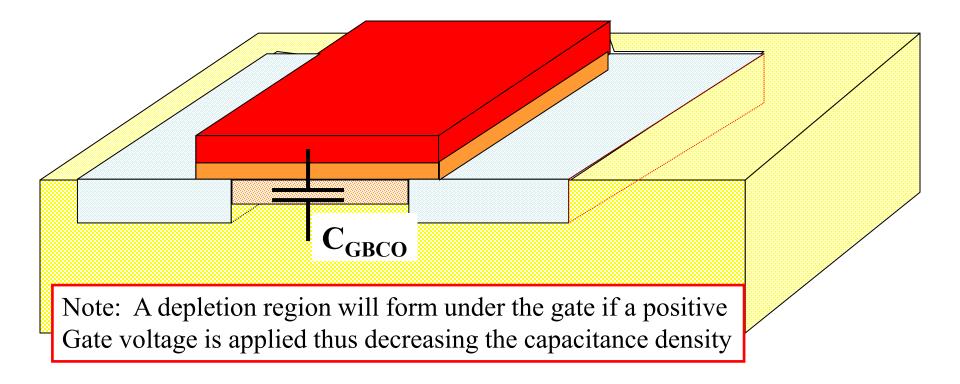
- 1. Fixed Capacitors
 - a. Fixed Geometry
 - b. Junction
- **2**. Operating Region Dependent

Parasitic Capacitors in MOSFET Operation Region Dependent -- Cutoff



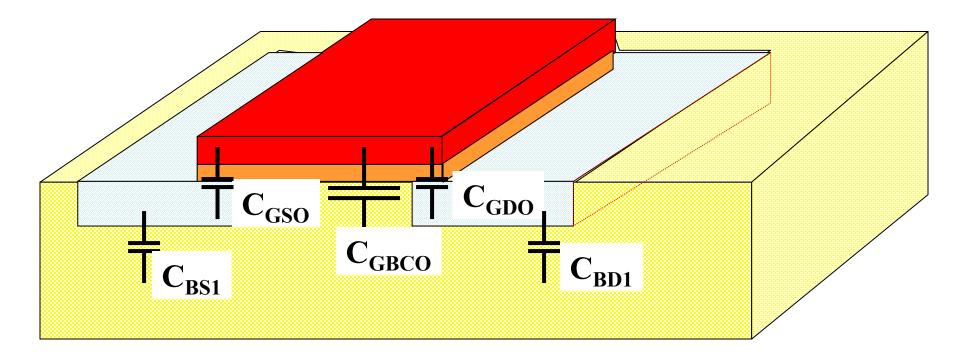
Cutoff Capacitor: C_{GBCO}

Parasitic Capacitors in MOSFET Operation Region Dependent -- Cutoff



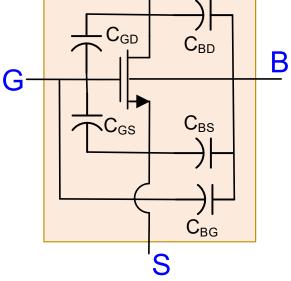
Cutoff Capacitor: C_{GBCO}

Parasitic Capacitors in MOSFET Operation Region Dependent and Fixed -- Cutoff



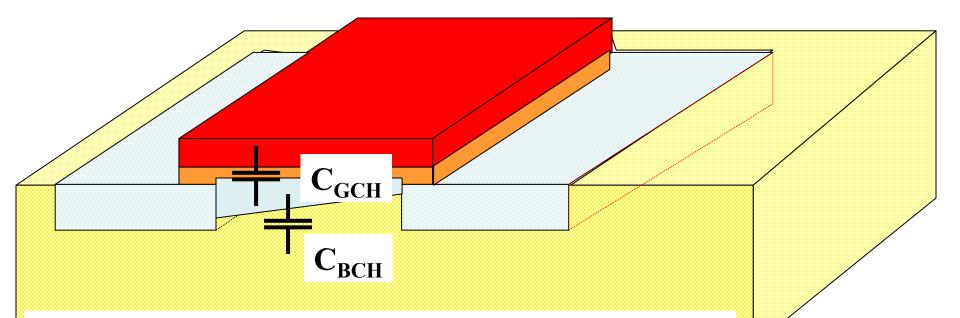
Overlap Capacitors: C_{GDO} , C_{GSO} Junction Capacitors: C_{BS1} , C_{BD1} **Cutoff Capacitor: C_{GBCO}**

Parasitic Capacitance Summary



	Cutoff	Ohmic	Saturation
C _{GS}	CoxWL _D		
	CoxWL _D		
C _{BG}	CoxWL (or less)		
C _{BS}	C _{BOT} A _S +C _{SW} P _S		
C _{BD}	C _{BOT} A _D +C _{SW} P _D		

Parasitic Capacitors in MOSFET Operation Region Dependent -- Ohmic

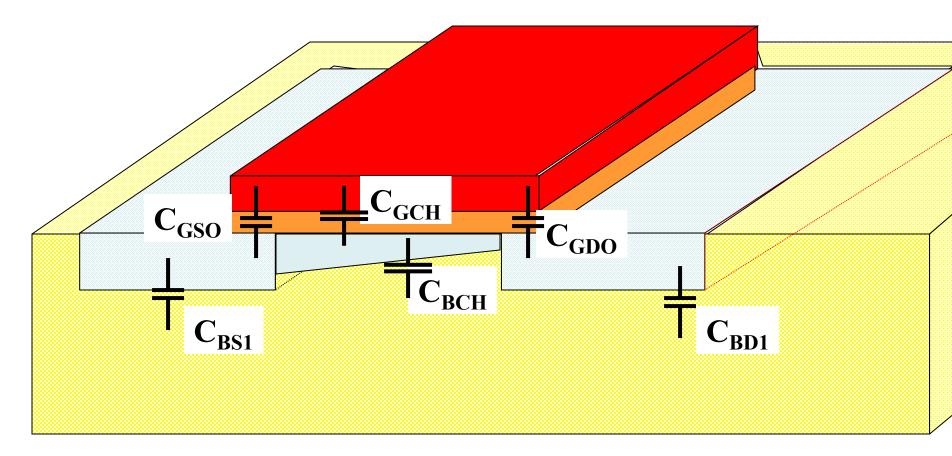


Note: The Channel is not a node in the lumped device model so can not directly include this distributed capacitance in existing models

Note: The distributed channel capacitance is usually lumped and split evenly between the source and drain nodes

Ohmic Capacitor: C_{GCH} , C_{BCH}

Parasitic Capacitors in MOSFET Operation Region Dependent and Fixed -- Ohmic

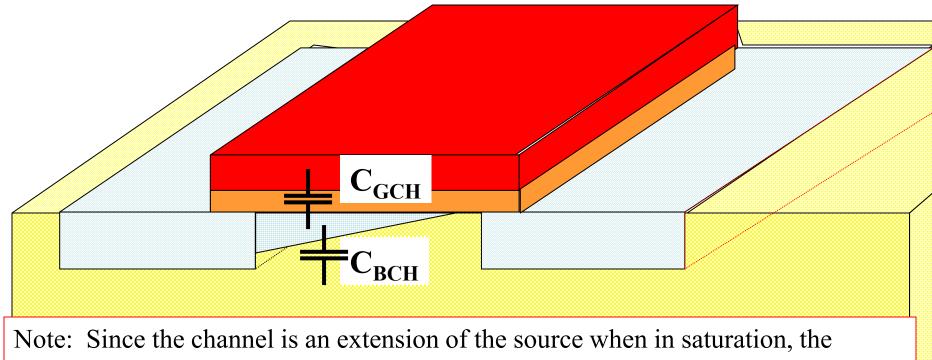


Overlap Capacitors: C_{GDO} , C_{GSO} Junction Capacitors: C_{BS1} , C_{BD1} **Ohmic Capacitor:** C_{GCH} , C_{BCH}

	Cutoff	Ohmic	Saturation
C _{GS}	CoxWL _D	0.5CoxWL	
C_{GD}	CoxWL _D	0.5CoxWL	
C _{BG}	CoxWL (or less)	0	
C _{BS}	C _{BOT} A _S +C _{SW} P _S	C _{BOT} A _S +C _{SW} P _S +0.5WLC _{BOTCH}	
	$C_{BOT}A_{D}+C_{SW}P_{D}$	C _{BOT} A _D +C _{SW} P _D +0.5WLC _{BOTCH}	

S

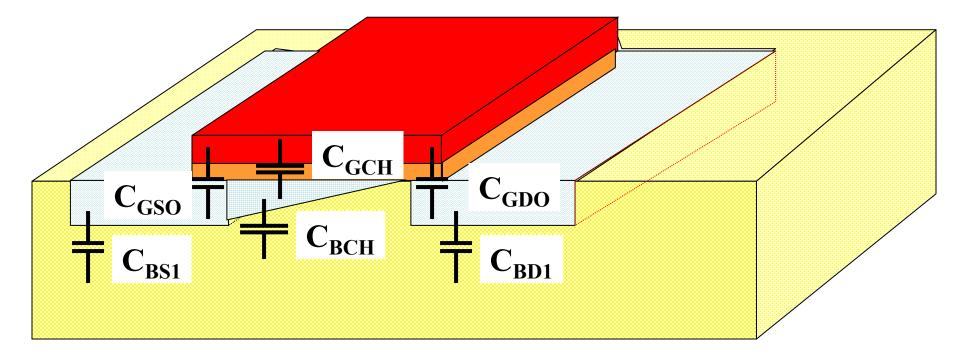
Parasitic Capacitors in MOSFET Operation Region Dependent -- Saturation



distributed capacitors to the channel are generally lumped to the source node

Saturation Capacitors: C_{GCH}, C_{BCH}

Parasitic Capacitors in MOSFET Operation Region Dependent and Fixed --Saturation



Overlap Capacitors: C_{GDO} , C_{GSO} Junction Capacitors: C_{BS1} , C_{BD1} **Saturation Capacitors:** C_{GCH} , C_{BCH}

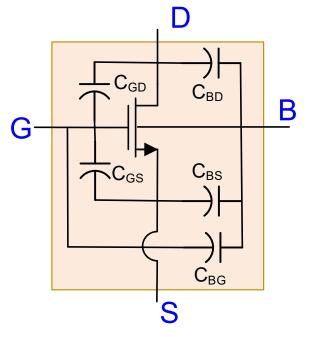
- $2/3 C_{OX}WL$ is often attributed to C_{GCH} to account for LD and saturation
- This approximation is reasonable for minimum-length devices but not so good for longer devices

Parasitic Capacitance Summary C_{GD} C_{BD} В G C_{BS} **∇**C_{GS} C_{BG}

	Cutoff	Ohmic	Saturation		
C _{GS}	CoxWL _D	0.5C _{OX} WL	CoxWL _D +(2/3)C _{OX} WL		
	CoxWL _D	0.5C _{OX} WL	CoxWL _D		
C _{BG}	CoxWL (or less)	0	0		
C _{BS}	$C_{BOT}A_{S}+C_{SW}P_{S}$	C _{BOT} A _S +C _{SW} P _S +0.5WLC _{BOTCH}	С _{вот} А _S +C _{SW} P _S +(2/3)WLC _{вотсн}		
C _{BD}	$C_{BOT}A_{D}+C_{SW}P_{D}$	C _{BOT} A _D +C _{SW} P _D +0.5WLC _{BOTCH}	$C_{BOT}A_{D}+C_{SW}P_{D}$		

S

Parasitic Capacitance Summary



	Cutoff	Ohmic	Saturation
C _{GS}	CoxWL _D	0.5C _{OX} WL	CoxWL _D +(2/3)C _{OX} WL
C_{GD}	CoxWL _D	0.5C _{OX} WL	CoxWL _D
	CoxWL (or less)	0	0
C _{BS}	$C_{BOT}A_S + C_{SW}P_S$	C _{BOT} A _S +C _{SW} P _S +0.5WLC _{BOTCH}	C _{BOT} A _S +C _{SW} P _S +(2/3)WLC _{BOTCH}
	$C_{BOT}A_D + C_{SW}P_D$	C _{BOT} A _D +C _{SW} P _D +0.5WLC _{BOTCH}	$C_{BOT}A_{D}+C_{SW}P_{D}$



Stay Safe and Stay Healthy !

End of Lecture 36